

“Epitaxial chemical vapor deposition of silicon on an oxygen monolayer on Si(100) substrates”. Delabie A, Jayachandran S, Caymax M, Loo R, Maggen J, Pourtois G, Douhard B, Conard T, Meersschart J, Lenka H, Vandervorst W, Heyns M; ECS solid state letters **2**, P104 (2013). <http://doi.org/10.1149/2.009311ssl>